

Fundamental Study of Metal/Oxide/Metal Memristor Physics and Device Optimization

Sandia National Laboratories

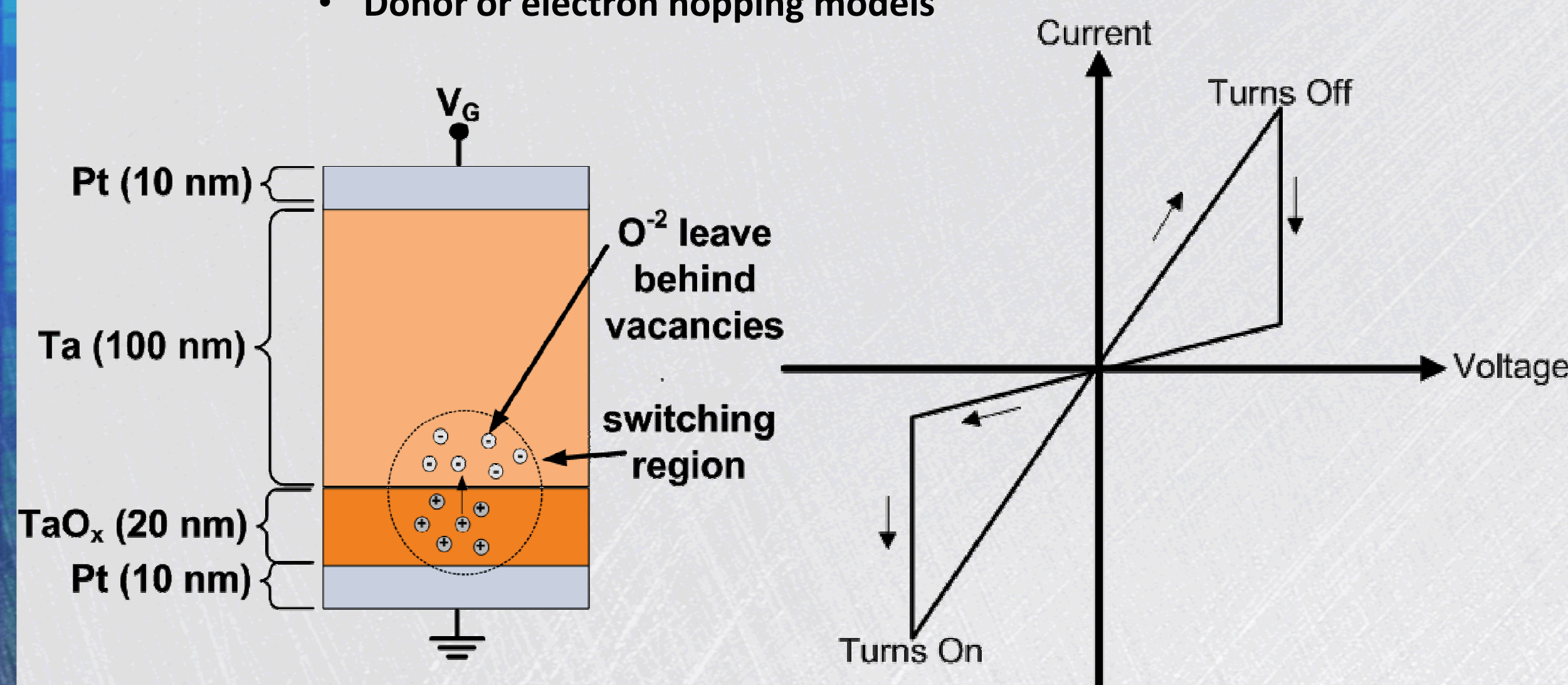
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Early Career R&D Program

Problem

- The Memristor or Resistive/Redox RAM (RRAM) is one of the most promising replacements for Flash, DRAM, and even SRAM memories
- Poor physical understanding of switching action has limited the use of this technology
- Problem: Insufficient understanding of switching mechanism**
- Current working theories:
 - Conductivity modulated by O^{2-} anion migration
 - Filament formation
 - Donor or electron hopping models

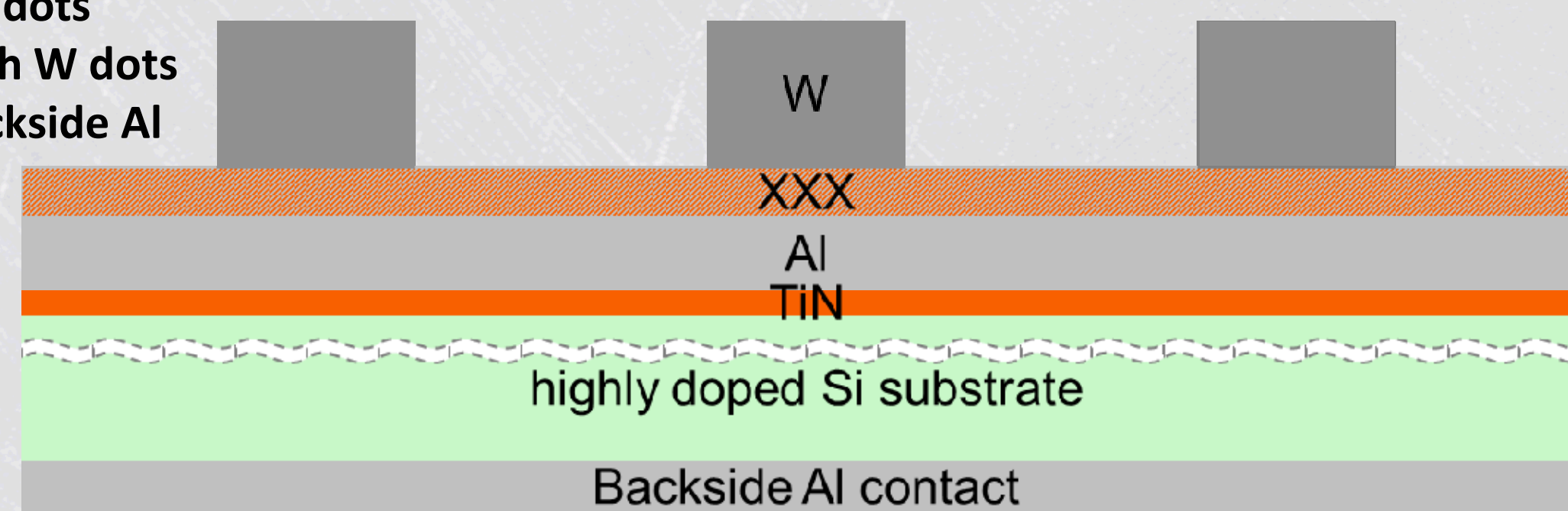


Approach

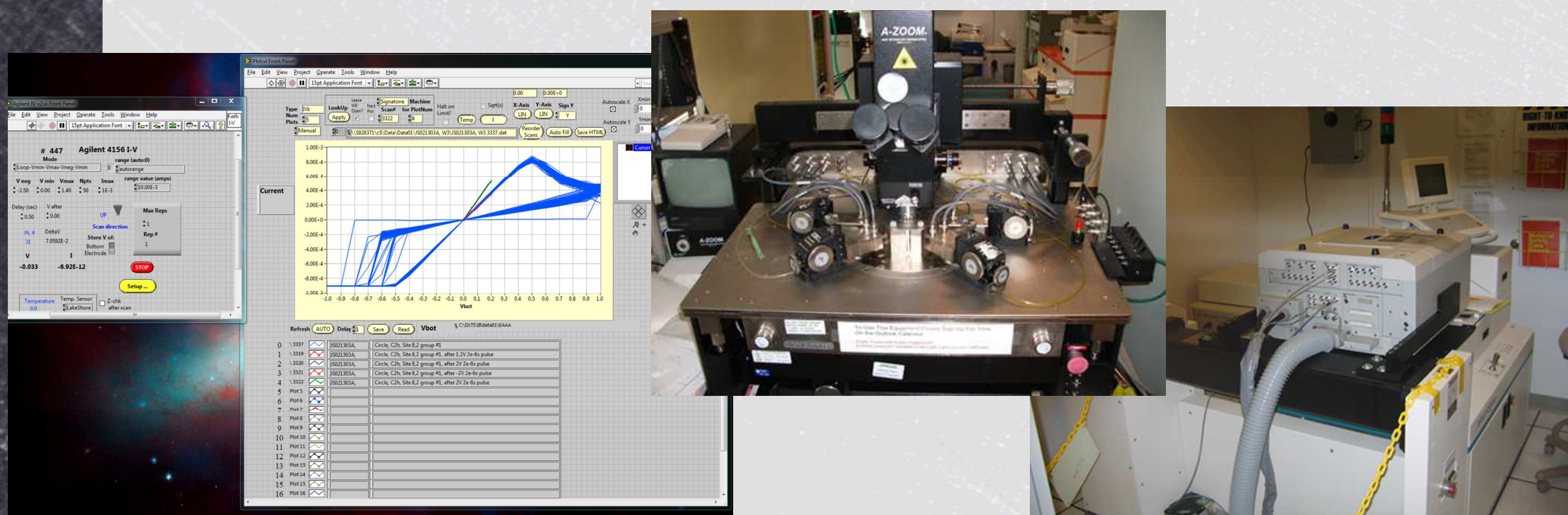
- Project Plan: Make memristors and use electrical characterization and modeling to understand switching**
- Focus on transition metal oxide (TMO) memristors
- Initial major risk – fabricating inexpensive but stable, working memristors
- Fabrication Approach: Two methods of device fabrication**
 - Sol-gel ZnO deposition on TMO substrate
 - Simple MESAFab flow to create metal/oxide/metal capacitors

MESAFab Flow

- Dep blanket TiN/Al
- Deposit metal oxide (XXX)
- Dep top ~7k W
- Pattern dots
- Wet etch W dots
- Dep backside Al



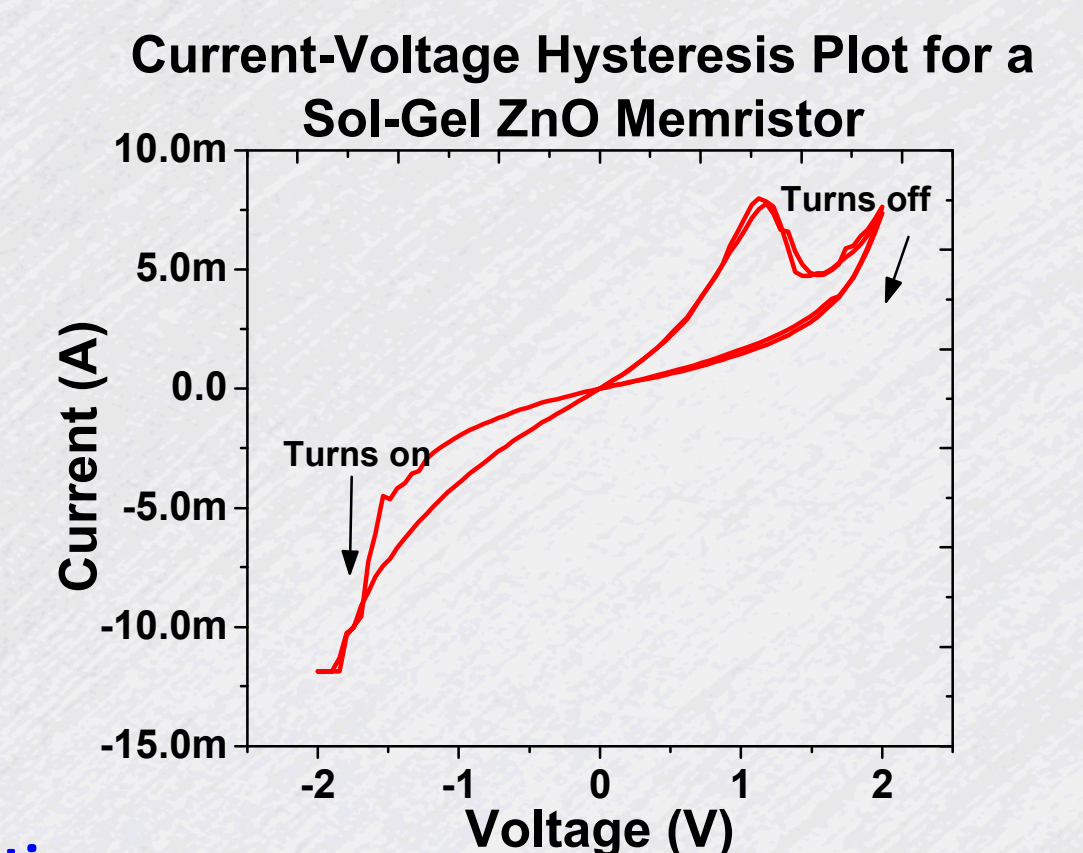
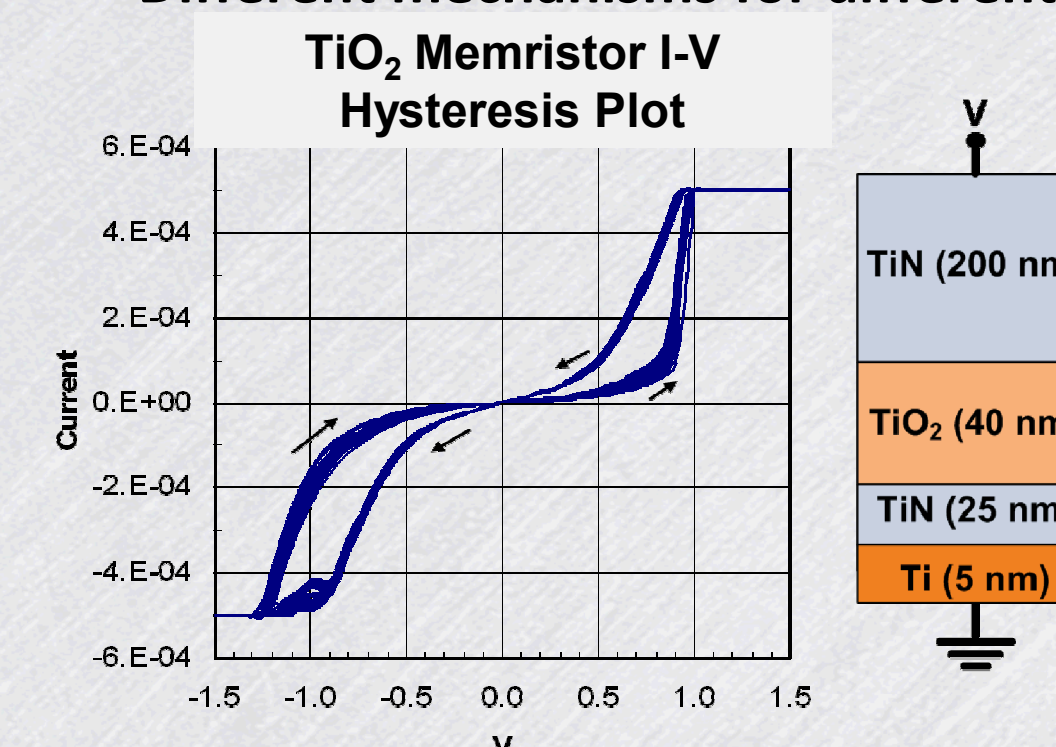
- Electrical Characterization Approach: Match a Common Insulator Conduction Mechanism**
- Examples: Ohmic, Ionic, Tunneling, Frenkel-Poole, Schottky Emission
- 2 Main Factors:
 - Current – Voltage Relationship
 - Current – Temperature Relationship
- Make use of 1748 rad-hard CMOS/advance device parametric test lab and Robert Fleming's extensive LabVIEW test suite



Results

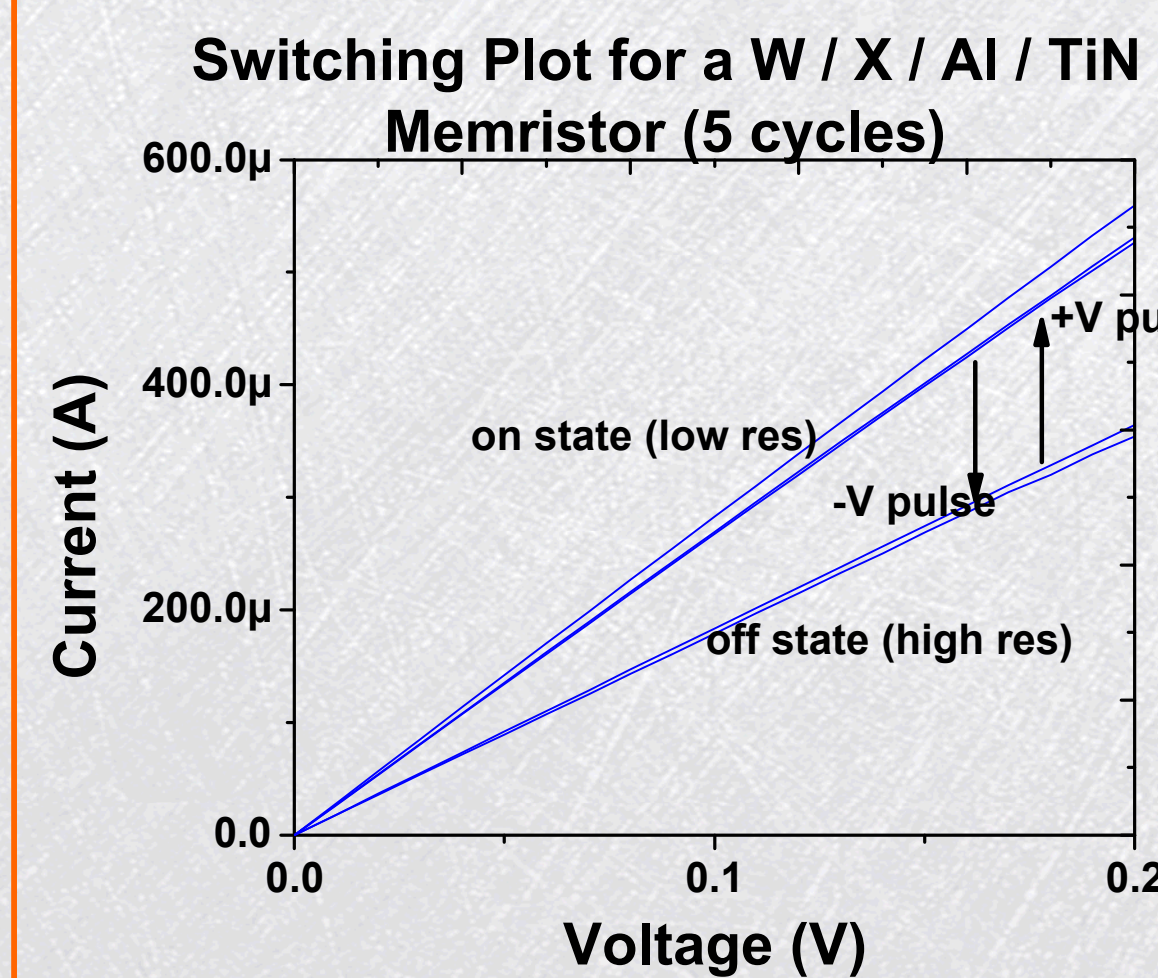
Each fabrication approach resulted in working devices:

- Chemistry lab: Sol-gel ZnO demonstrated (TiO_2 possible also)
- Fab: TiO_2 , WO, and a new, promising material demonstrated, TaOx samples from HP and in progress in uFab
- Variety of electrical characteristics for on and off I-V curves
- Different mechanisms for different materials?

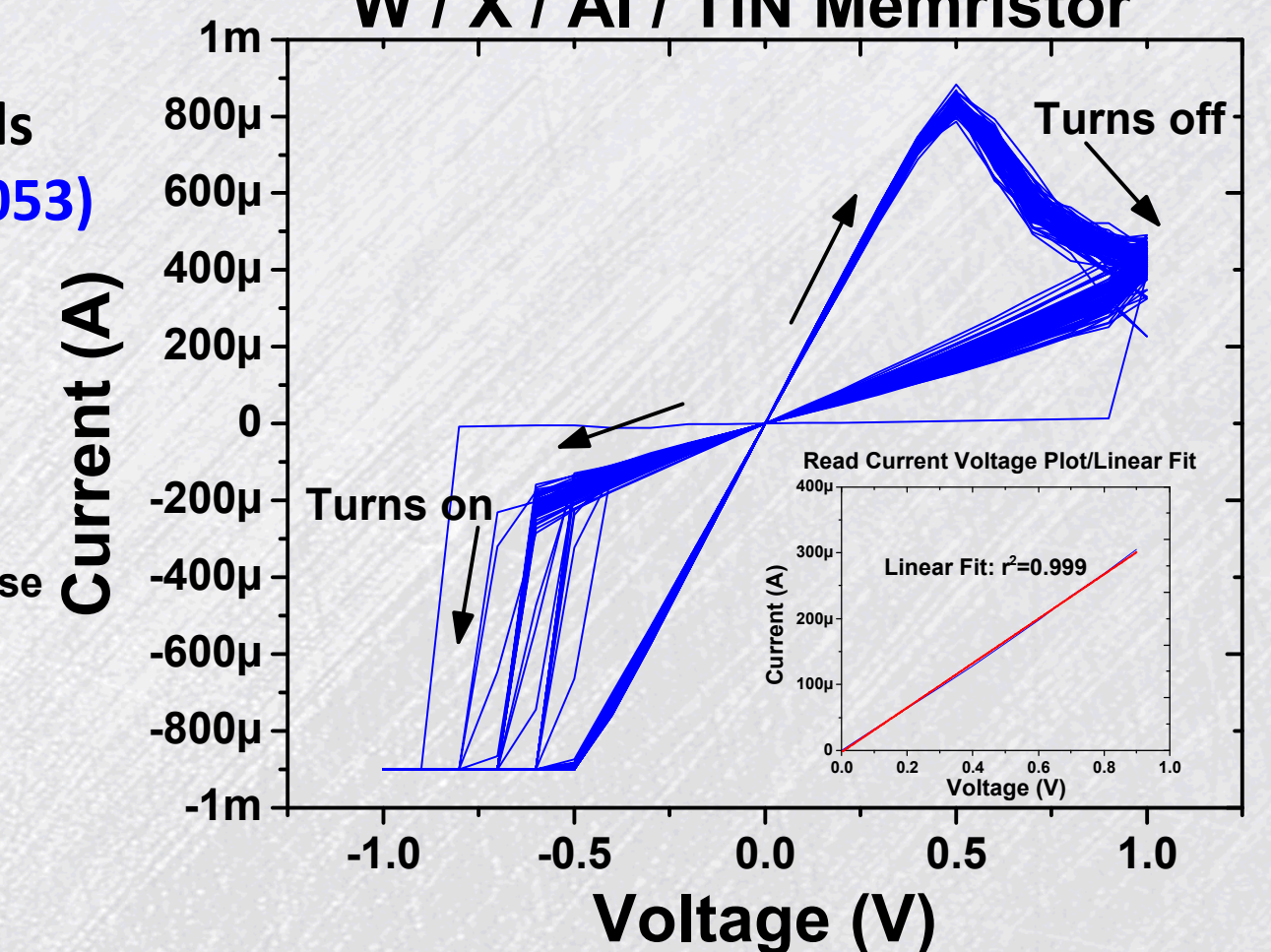


Invented new memristor with promising characteristics

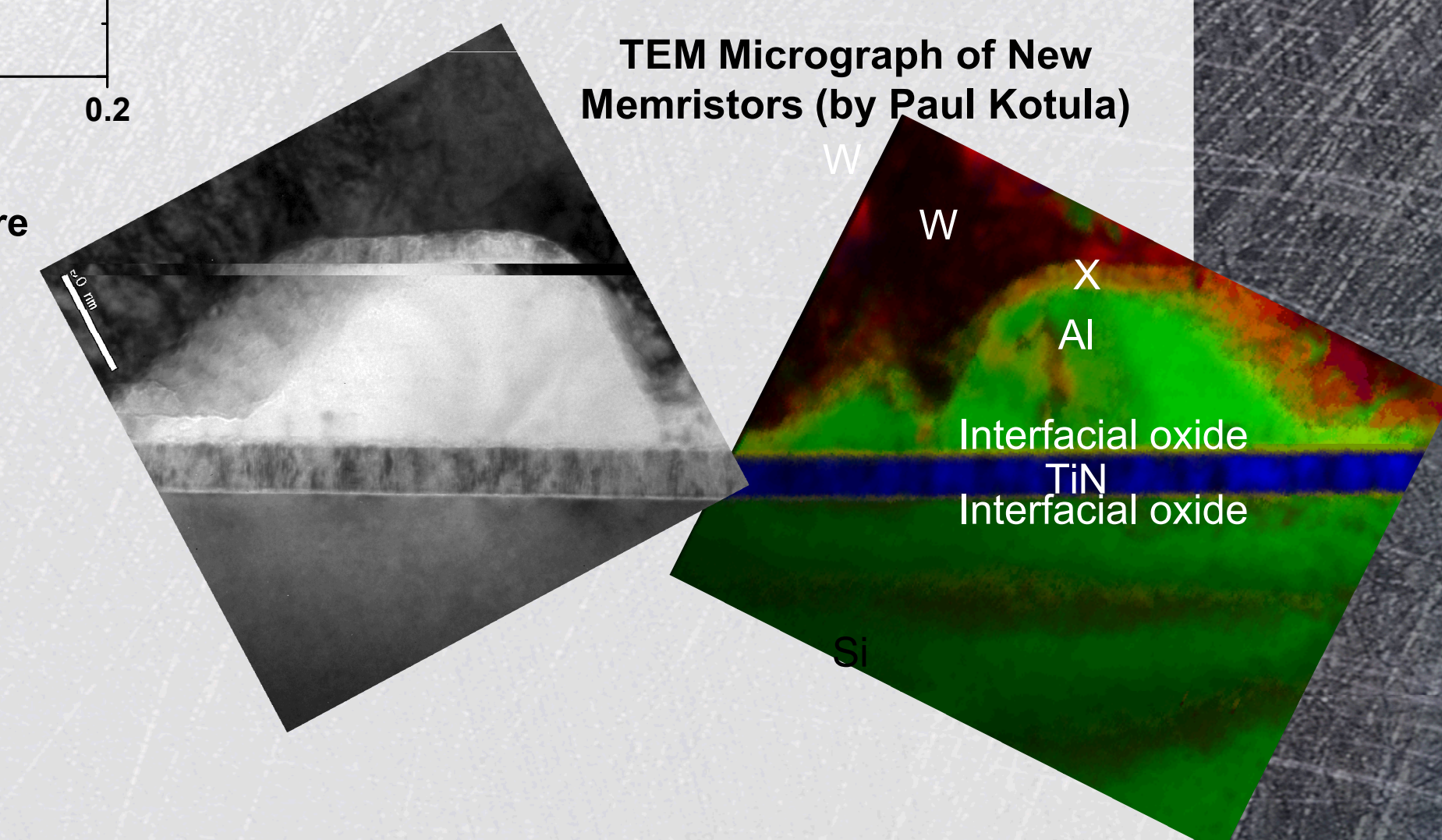
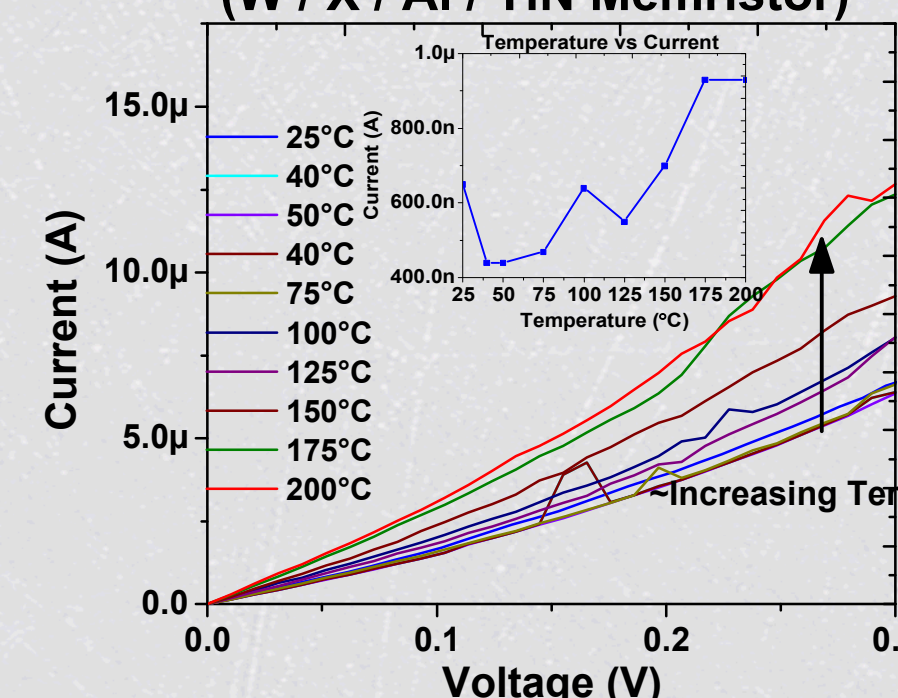
- 150 cycles, on/off pulsing demonstrated
- Highly linear I-V – Ohmic conduction?
- High on/off ratio possible
- New material questions current models
- TA submitted for new material (SD 12053)**



Current-Voltage Hysteresis Plot for a W / X / Al / TiN Memristor



Read Current-Voltage vs Temperature (W / X / Al / TiN Memristor)



Need a combination of physical and electrical characterization to understand switching!

- New NTM LDRD has been proposed and accepted to study physics of memristor switching

Significance

- Sandia has gained the ability to fabricate memristors from a number of materials
- A new memristor has been invented (SD 12053)
- Electrical modeling reveals different likely mechanisms for different materials
- Need a combination of physical and electrical characterization to understand switching!
- Memristors represent a new technology with major potential in numerous applications
 - Flash, DRAM, SRAM replacement, rad-hard memory, neuromorphic systems, and national security applications
- Two new follow-on LDRDs have been Funded for FY12 to continue and expand this work:
 - NTM LDRD to study physics of switching in TaOx memristors
 - Cyber security LDRD
 - One of the disruptive memory technologies for the Exascale Grand Challenge
- Other activities initiated by this work:
 - CRADA with Industrial Research Lab
 - Two external funded projects and major proposals
 - Collaborations initiated – Arizona State University, Boston University, and Industrial Partners

